

Electronic Supplementary Information

Effect of crystallinity on photocatalytic performance of Co_3O_4 water-splitting cocatalyst

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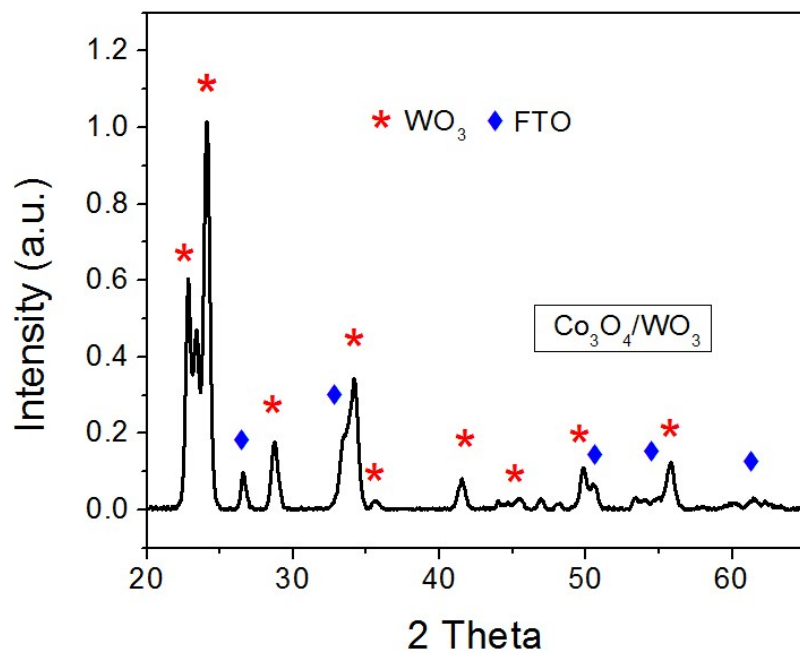


Figure S1. XRD spectra of 1 layer Co_3O_4 (annealed at 500 °C) on WO_3 . Only WO_3 and FTO are detected, as the XRD is not sensitive enough to detect the ultra-thin Co_3O_4 layer.

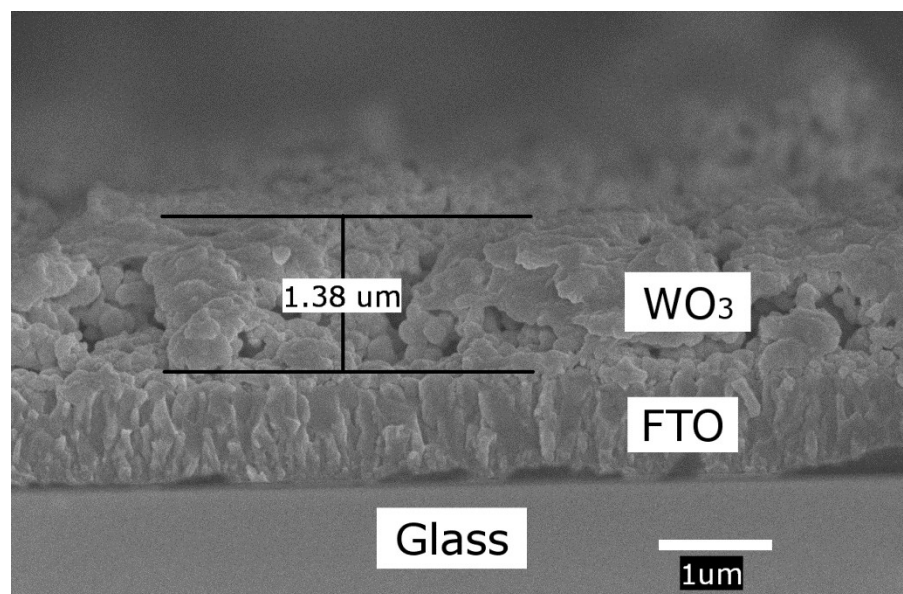


Figure S2. Cross-sectional view of $\text{Co}_3\text{O}_4/\text{WO}_3$ film

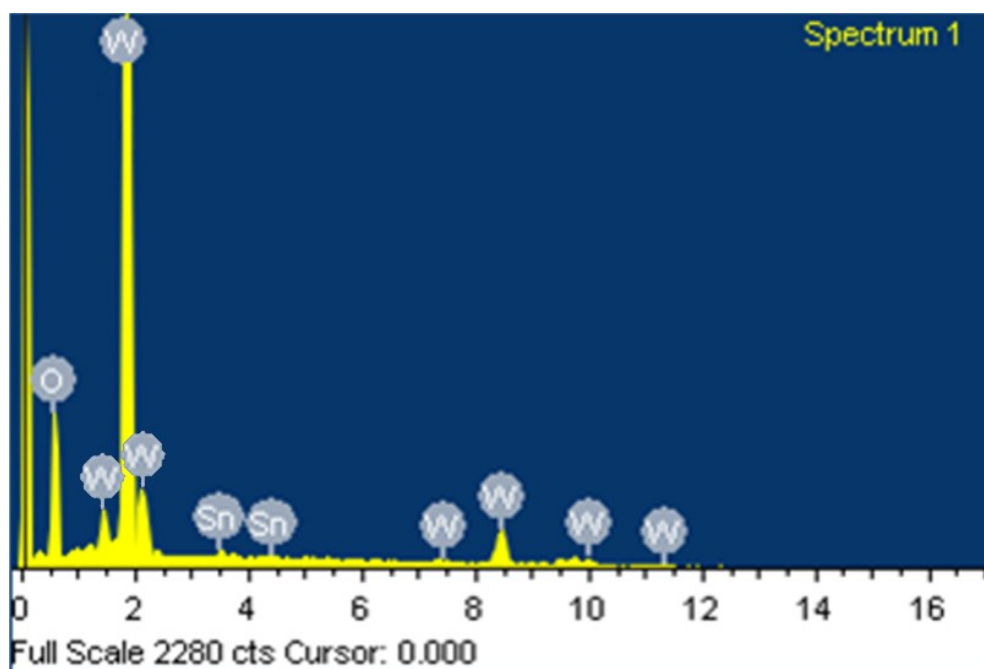


Figure S3. EDX analysis of $\text{Co}_3\text{O}_4/\text{WO}_3$ film on FTO.

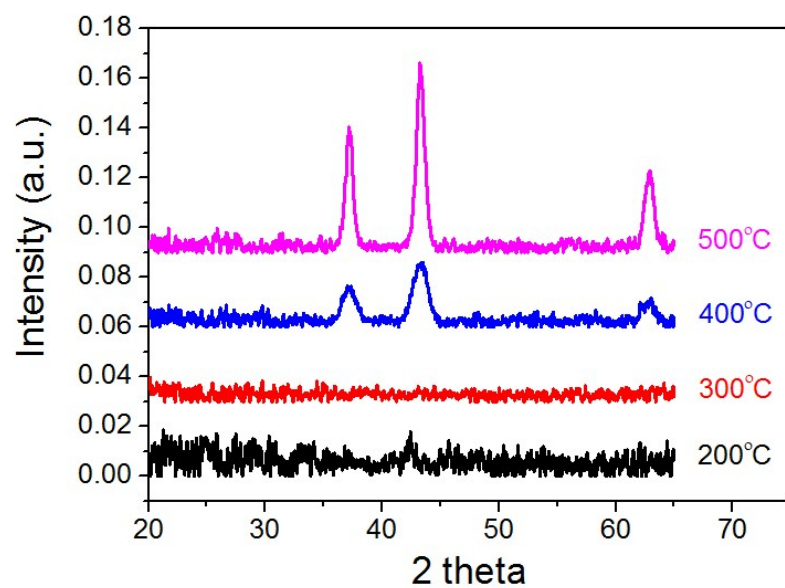


Figure S4. XRD spectra of NiO_x film on silicon at different annealing temperature.

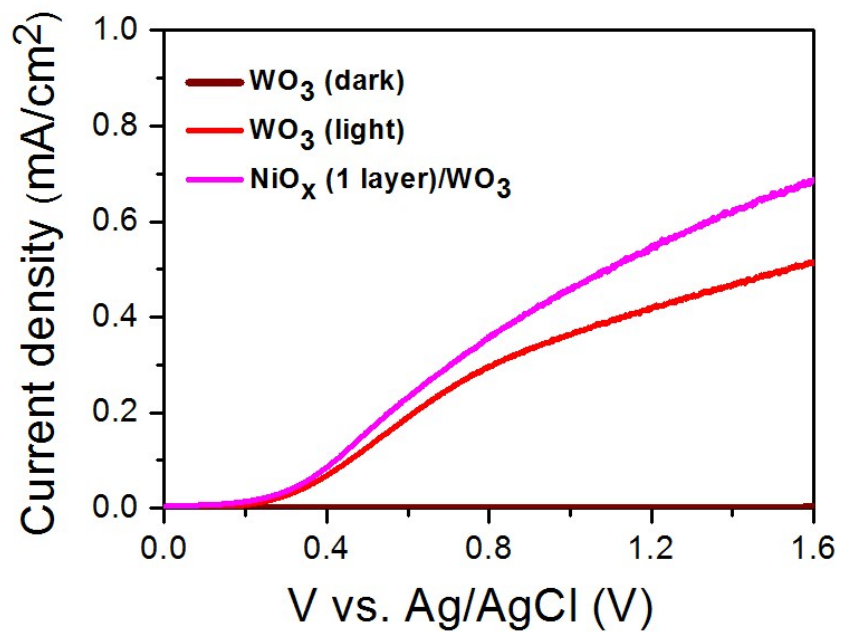


Figure S5. Photocurrent density of bare WO₃, and NiO_x/WO₃ (cocatalyst annealed at 350 °C).

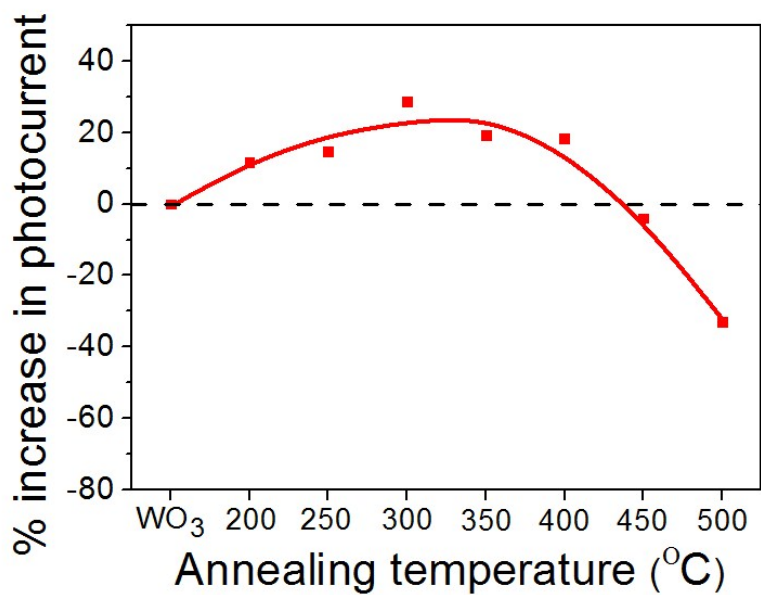


Figure S6. Percentage change in photocurrent (with respect to bare WO₃) with cocatalyst annealing temperature for NiO_x/WO₃ film at 1.2 V vs Ag/AgCl.